Fabrication of Ultralow Density Quantum Dots by Droplet Etching Epitaxy

Jiang Wu1,\*, Zhiming M. Wang2,\*, Xinlei Li3, Yuriy I. Mazur4, and Gregory J. Salamo4

1 Department of Electronic and Electrical Engineering, University College London, Torrington Place, London WC1E 7JE, United Kingdom

2 Institute of Fundamental and Frontier Sciences, University of Electronic Science and Technology of China, Chengdu 610054, People’s Republic of China

3 MOE Key Laboratory of Laser Life Science & Institute of Laser Life Science, College of Biophotonics, South China Normal University, Guangzhou 510631, P. R. China

4 Institute for Nanoscience and Engineering, University of Arkansas, Fayetteville, Arkansas 72701, United States of America

\* [Jiang.wu@ucl.ac.uk](mailto:Jiang.wu@ucl.ac.uk) and [zhmwang@uestc.edu.cn](mailto:zhmwang@uestc.edu.cn)

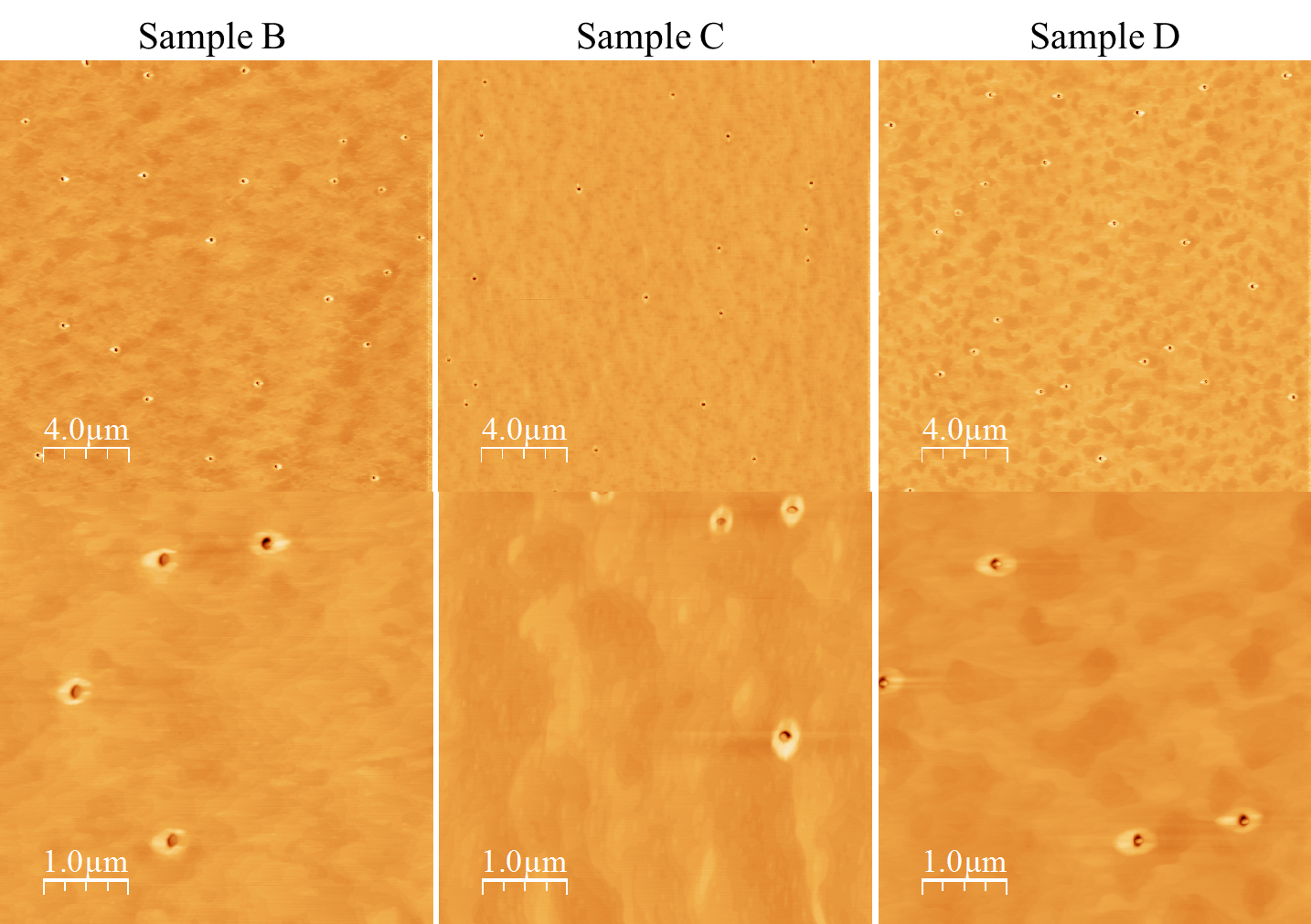


Figure S1. AFM images of sample B (0.9 ML InAs), sample C (1.2 ML InAs), and sample D (1.35 ML InAs). Top row: 20 × 20 µm2; bottom row: 5 × 5 µm2.